Lecture 12: MOS Transistor Models

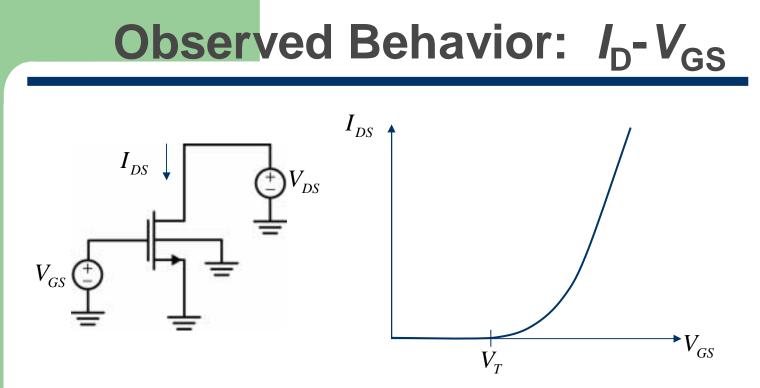
Prof. Niknejad



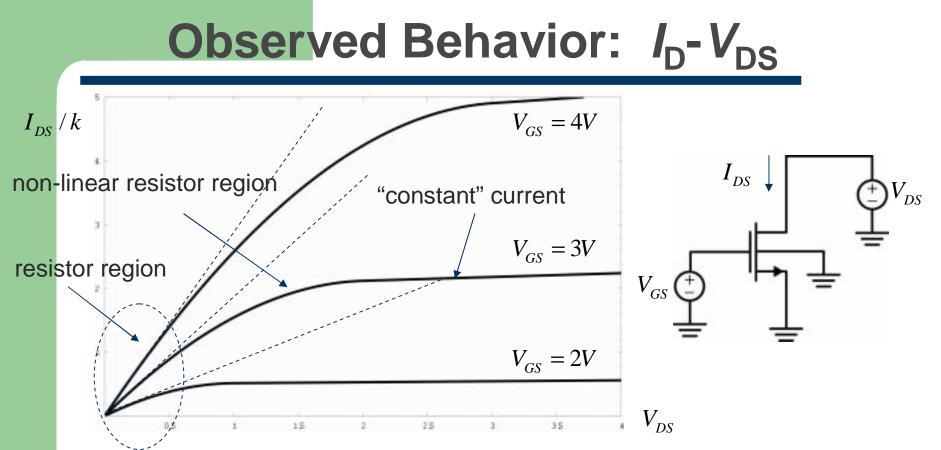
University of California, Berkeley

Lecture Outline

- MOS Transistors (4.3 4.6)
 - I-V curve (Square-Law Model)
 - Small Signal Model (Linear Model)



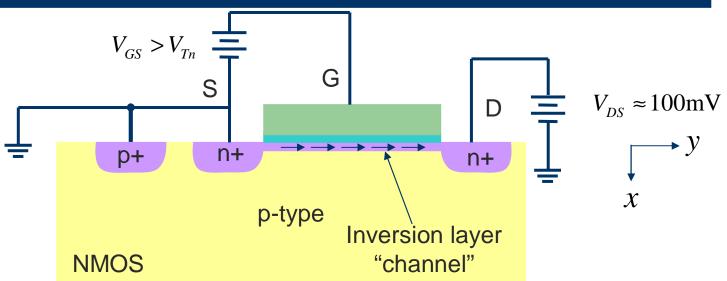
- Current zero for negative gate voltage
- Current in transistor is very low until the gate voltage crosses the threshold voltage of device (same threshold voltage as MOS capacitor)
- Current increases rapidly at first and then it finally reaches a point where it simply increases linearly



- For low values of drain voltage, the device is like a resistor
- As the voltage is increases, the resistance behaves non-linearly and the rate of increase of current slows
- Eventually the current stops growing and remains essentially constant (current source)

EECS 105 Fall 2003, Lecture 12

"Linear" Region Current



- If the gate is biased above threshold, the surface is inverted
- This inverted region forms a channel that connects the drain and gate
- If a drain voltage is applied positive, electrons will flow from source to drain

MOSFET: Variable Resistor

• Notice that in the linear region, the current is proportional to the voltage

$$I_{DS} = \frac{W}{L} \mu_n C_{ox} (V_{GS} - V_{Tn}) V_{DS}$$

• Can define a voltage-dependent resistor

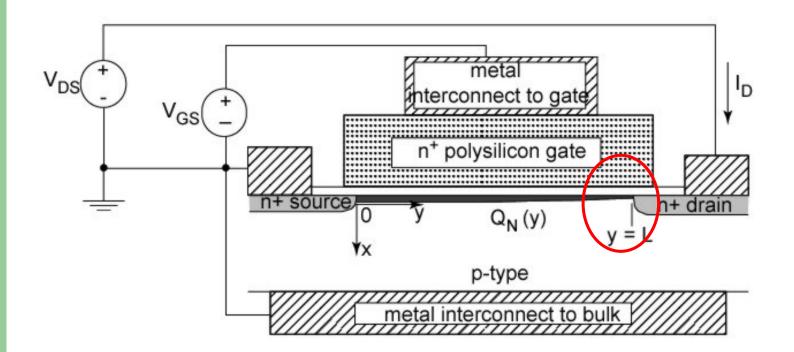
$$R_{eq} = \frac{V_{DS}}{I_{DS}} = \frac{1}{\mu_n C_{ox} (V_{GS} - V_{Tn})} \left(\frac{L}{W}\right) = R_{\Box} (V_{GS}) \frac{L}{W}$$

• This is a nice variable resistor, electronically tunable!

EECS 105 Fall 2003, Lecture 12

Finding $I_D = f(V_{GS}, V_{DS})$

• Approximate inversion charge $Q_N(y)$: drain is higher than the source \rightarrow less charge at drain end of channel



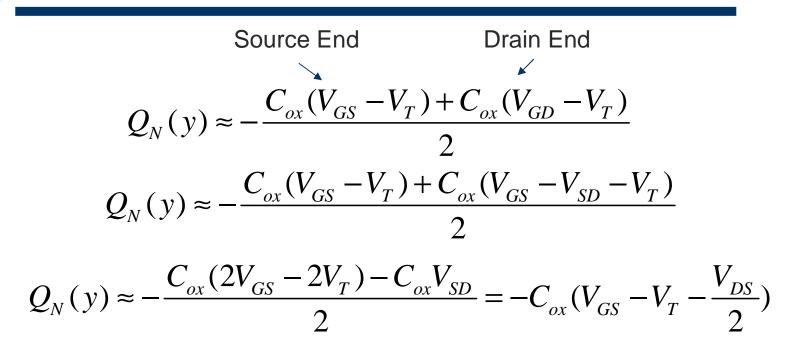
Inversion Charge at Source/Drain

$$Q_{N}(y) \approx Q_{N}(y=0) + Q_{N}(y=L)$$

$$Q_{N}(y=0) = -C_{ox}(V_{GS} - V_{Tn}) \qquad Q_{N}(y=L) = -C_{ox}(V_{GD} - V_{Tn})$$

$$Q_{D} = V_{GS} - V_{DS}$$

Average Inversion Charge



- Charge at drain end is lower since field is lower
- Simple approximation: In reality we should integrate the total charge minus the bulk depletion charge across the channel

Drift Velocity and Drain Current

"Long-channel" assumption: use mobility to find v

$$v(y) = -\mu_n E(y) \approx -\mu_n (-\Delta V / \Delta y) = \frac{\mu_n V_{DS}}{L}$$

Substituting:

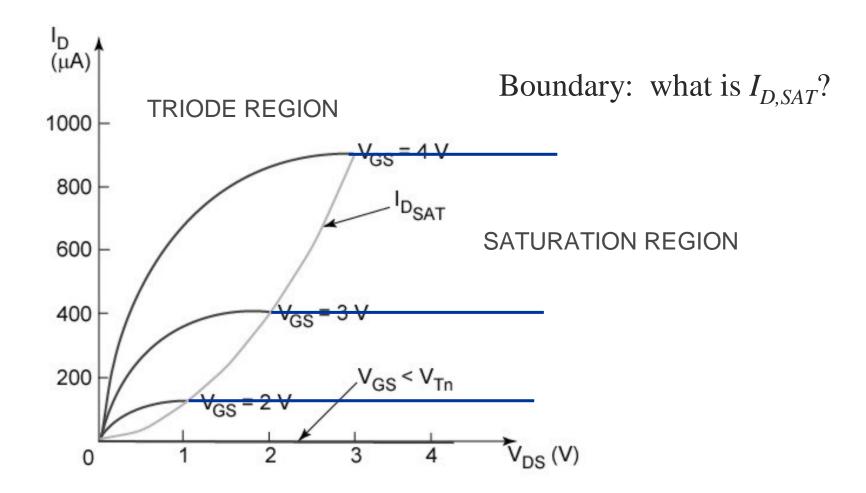
$$I_D = -WvQ_N \approx W\mu \frac{V_{DS}}{L}C_{ox}(V_{GS} - V_T - \frac{V_{DS}}{2})$$

$$I_D \approx \frac{W}{L} \mu C_{ox} (V_{GS} - V_T - \frac{V_{DS}}{2}) V_{DS}$$

Inverted Parabolas

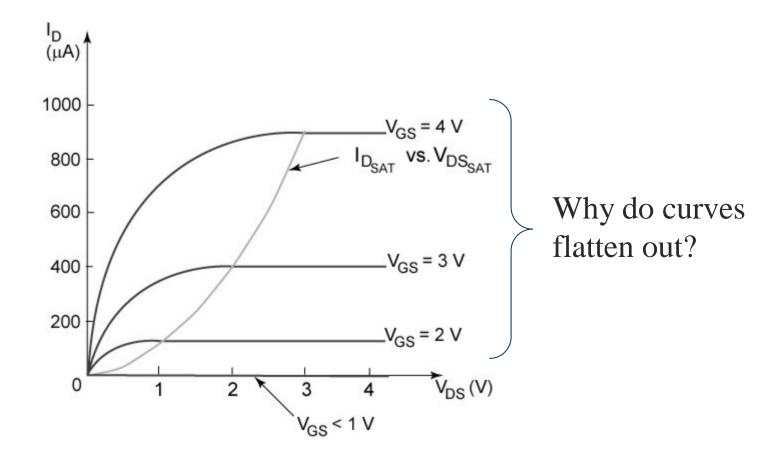
Department of EECS

Square-Law Characteristics



The Saturation Region

When $V_{DS} > V_{GS} - V_{Tn}$, there isn't any inversion charge at the drain ... according to our simplistic model



Square-Law Current in Saturation

Current stays at maximum (where $V_{DS} = V_{GS} - V_{Tn} = V_{DS,SAT}$)

$$I_{D} = \frac{W}{L} \mu C_{ox} (V_{GS} - V_{T} - \frac{V_{DS}}{2}) V_{DS}$$

$$I_{DS,sat} = \frac{W}{L} \mu C_{ox} (V_{GS} - V_T - \frac{V_{GS} - V_T}{2}) (V_{GS} - V_T)$$

$$I_{DS,sat} = \frac{W}{L} \frac{\mu C_{ox}}{2} (V_{GS} - V_T)^2$$

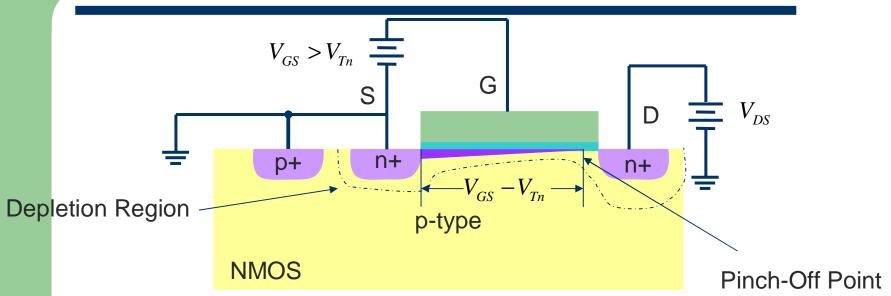
Measurement: I_D increases slightly with increasing V_{DS} model with linear "fudge factor"

$$I_{DS,sat} = \frac{W}{L} \frac{\mu C_{ox}}{2} (V_{GS} - V_T)^2 (1 + \lambda V_{DS})$$

Department of EECS

University of California, Berkeley

Pinching the MOS Transistors



- When $V_{\text{DS}} > V_{\text{DS,sat}}$, the channel is "pinched" off at drain end (hence the name "pinch-off region")
- Drain mobile charge goes to zero (region is depleted), the remaining elecric field is dropped across this high-field depletion region
- As the drain voltage is increases further, the pinch off point moves back towards source
- Channel Length Modulation: The effective channel length is thus reduced
 → higher I_{DS}

Linear MOSFET Model

Channel (inversion) charge: neglect reduction at drain

Velocity saturation defines $V_{DS,SAT} = E_{sat} L = \text{constant}$ Drain current:

$$I_{D,SAT} = -WvQ_N = -W(v_{sat})[-C_{ox}(V_{GS} - V_{Tn})],$$

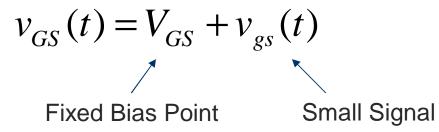
 $|E_{sat}| = 10^4 \text{ V/cm}, L = 0.12 \text{ }\mu\text{m} \rightarrow V_{DS,SAT} = 0.12 \text{ V!}$

$$I_{D,SAT} = v_{sat} W C_{ox} (V_{GS} - V_{Tn}) (1 + \lambda_n V_{DS})$$

Department of EECS

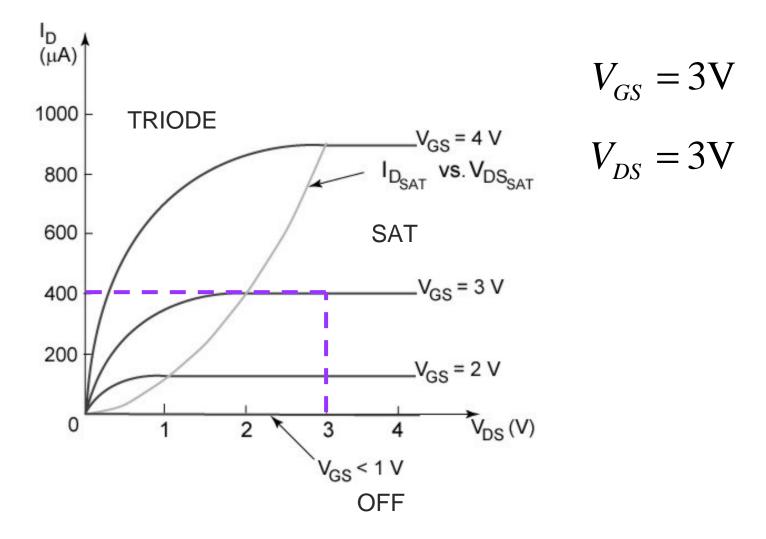
Why Find an Incremental Model?

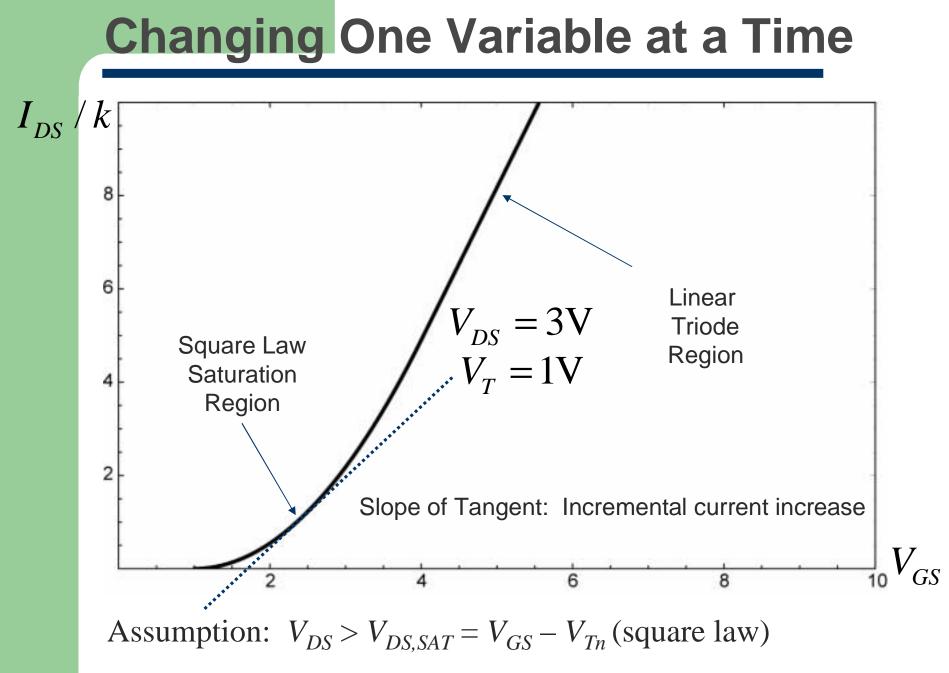
• Signals of interest in analog ICs are often of the form:



Direct substitution into $i_D = f(v_{GS}, v_{DS})$ is tedious AND doesn't include charge-storage effects ... pretty rough approximation

Which Operating Region?





University of California, Berkeley

The Transconductance g_m

Defined as the change in drain current due to a change in the *gate-source* voltage, with *everything else constant*

$$I_{DS,sat} = \frac{W}{L} \frac{\mu C_{ox}}{2} (V_{GS} - V_T)^2 (1 + \lambda V_{DS})$$

$$g_m = \frac{\Delta i_D}{\Delta v_{GS}} \bigg|_{V_{GS}, V_{DS}} = \frac{\partial i_D}{\partial v_{GS}} \bigg|_{V_{GS}, V_{DS}} = \mu C_{ox} \frac{W}{L} (V_{GS} - V_T) (1 + \lambda V_{DS})$$

$$g_m = \mu C_{ox} \frac{W}{L} (V_{GS} - V_T) \quad \leftarrow \quad \text{Gate Bias}$$

$$g_m = \mu C_{ox} \frac{W}{L} \sqrt{\frac{2I_{DS}}{W}} = \sqrt{2\mu C_{ox} \frac{W}{L}} I_{DS} \quad \leftarrow \quad \text{Drain Current Bias}$$

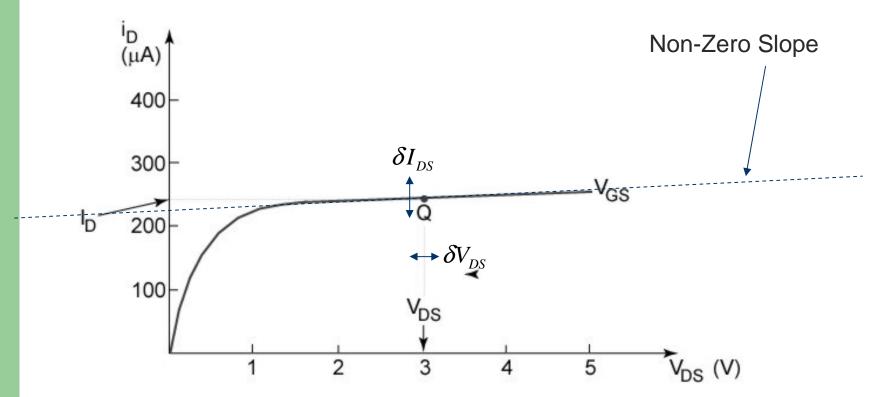
$$g_m = \frac{2I_{DS}}{(V_{GS} - V_T)} \quad \leftarrow \quad \text{Drain Current Bias and}$$

$$g_m = \frac{2I_{DS}}{(V_{GS} - V_T)} \quad \leftarrow \quad \text{Drain Current Bias and}$$

University of California, Berkeley

Output Resistance *r*_o

Defined as the inverse of the change in drain current due to a change in the *drain-source* voltage, with *everything else constant*



Evaluating r_o

$$i_{D} = \frac{W}{L} \frac{\mu C_{ox}}{2} (V_{GS} - V_{T})^{2} (1 + \lambda V_{DS})$$

$$r_{o} = \left(\frac{\partial i_{D}}{\partial v_{DS}}\Big|_{V_{GS}, V_{DS}}\right)^{-1}$$

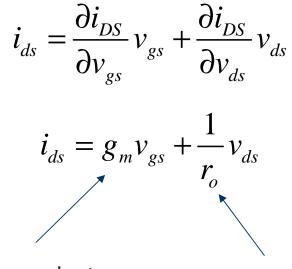
$$r_{0} = \frac{1}{\frac{W}{L} \frac{\mu C_{ox}}{2} (V_{GS} - V_{T})^{2} \lambda}$$

$$r_{0} \approx \frac{1}{\lambda I_{DS}}$$

Department of EECS

Total Small Signal Current

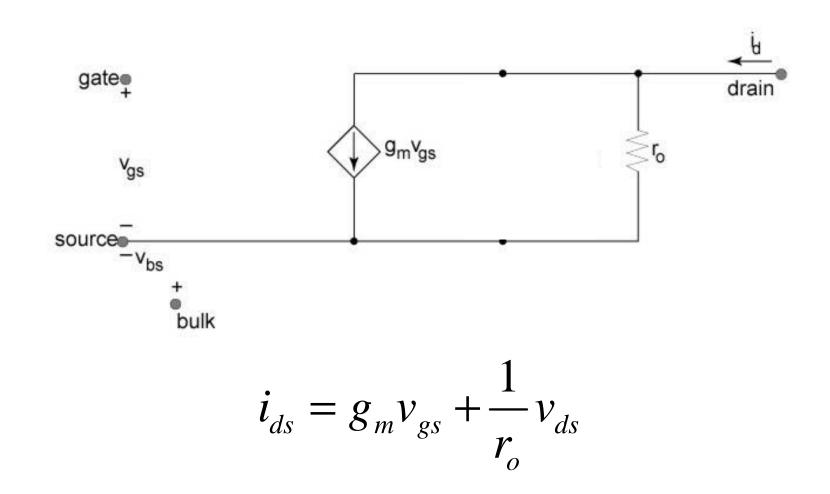
$$i_{DS}(t) = I_{DS} + i_{ds}$$



*Trans*conductance

Conductance

Putting Together a Circuit Model



Role of the Substrate Potential

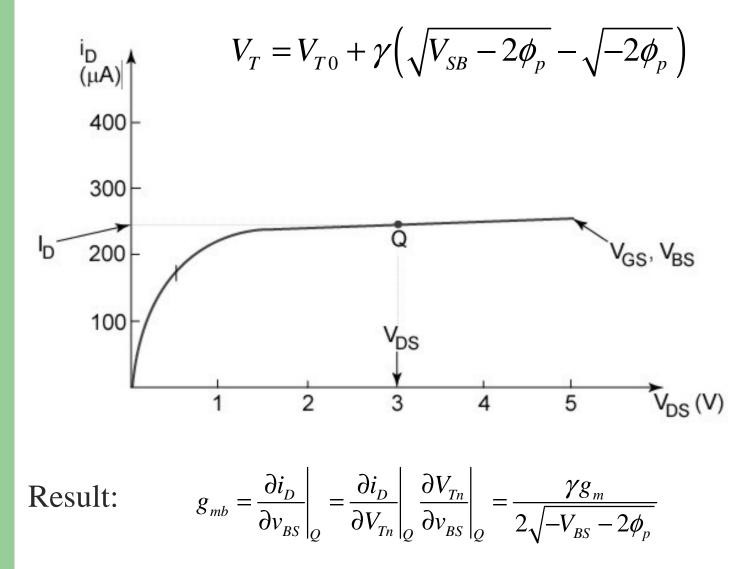
Need not be the source potential, but $V_B < V_S$

Effect: changes threshold voltage, which changes the drain current ... substrate acts like a "backgate"

$$g_{mb} = \frac{\Delta i_D}{\Delta v_{BS}} \bigg|_Q = \frac{\partial i_D}{\partial v_{BS}} \bigg|_Q$$

 $\mathbf{Q} = (V_{GS}, V_{DS}, V_{BS})$

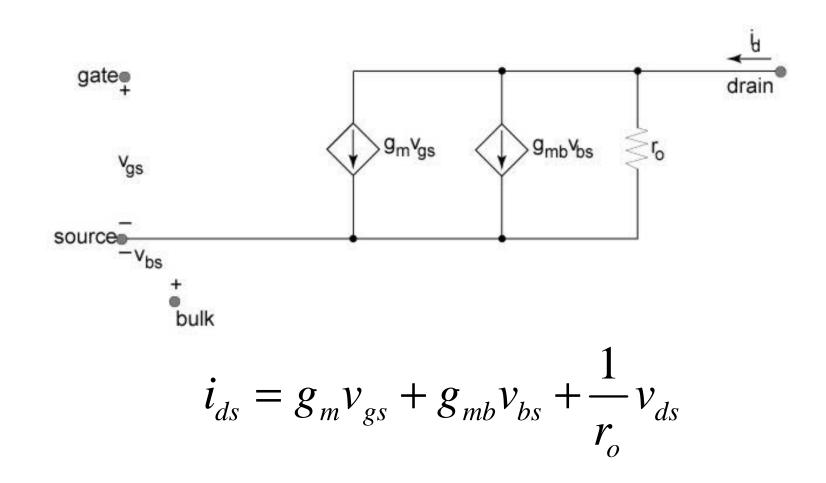
Backgate Transconductance

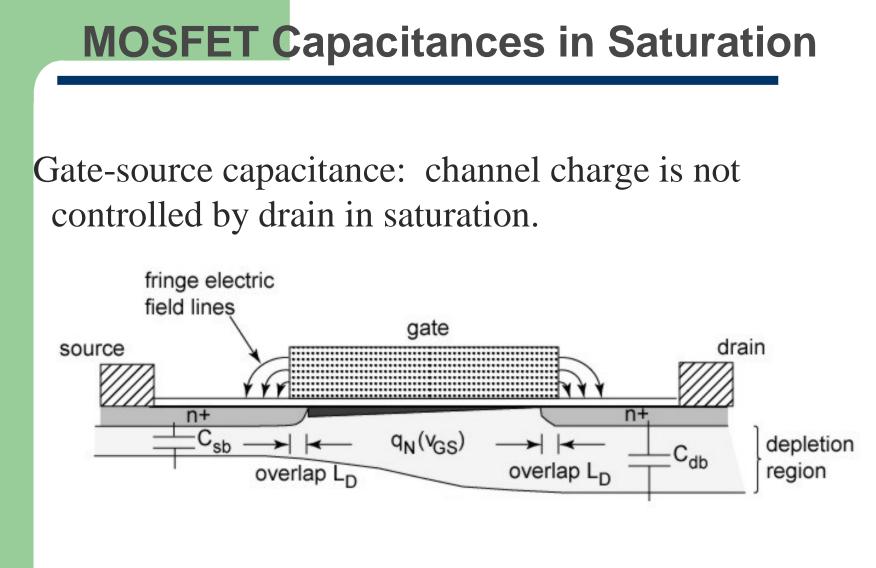


Department of EECS

University of California, Berkeley

Four-Terminal Small-Signal Model







Wedge-shaped charge in saturation \rightarrow effective area is (2/3)WL (see H&S 4.5.4 for details)

$$C_{gs} = (2/3)WLC_{ox} + C_{ov}$$

Overlap capacitance along source edge of gate \rightarrow

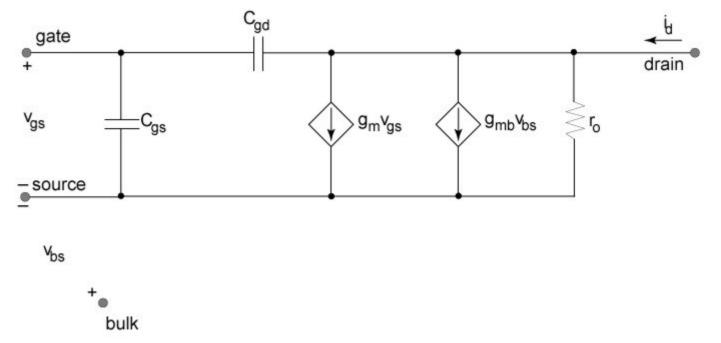
$$C_{ov} = L_D W C_{ox}$$

(Underestimate due to fringing fields)



Not due to change in inversion charge in channel

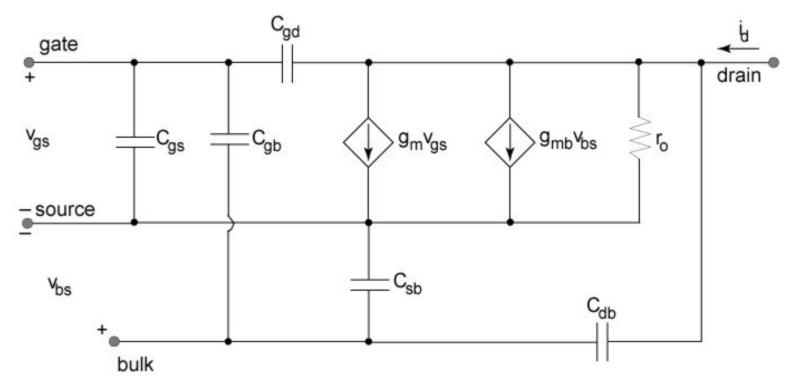
Overlap capacitance C_{ov} between drain and source is C_{gd}



Junction Capacitances

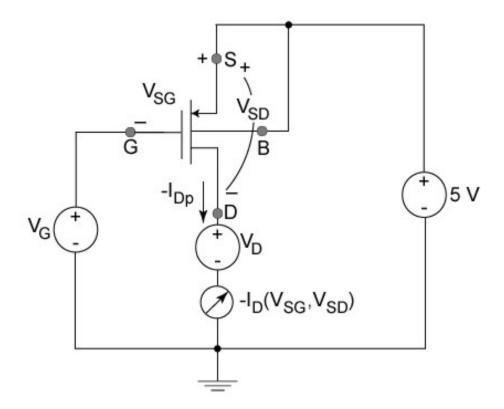
Drain and source diffusions have (different) junction capacitances since V_{SB} and $V_{DB} = V_{SB} + V_{DS}$ aren't the same

Complete model (without interconnects)

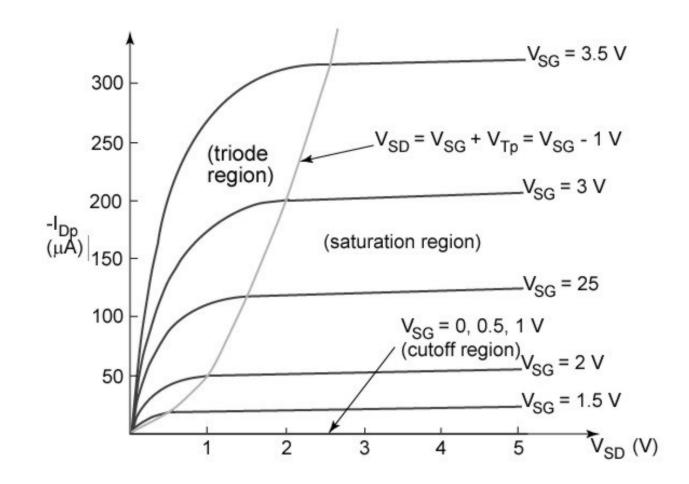


P-Channel MOSFET

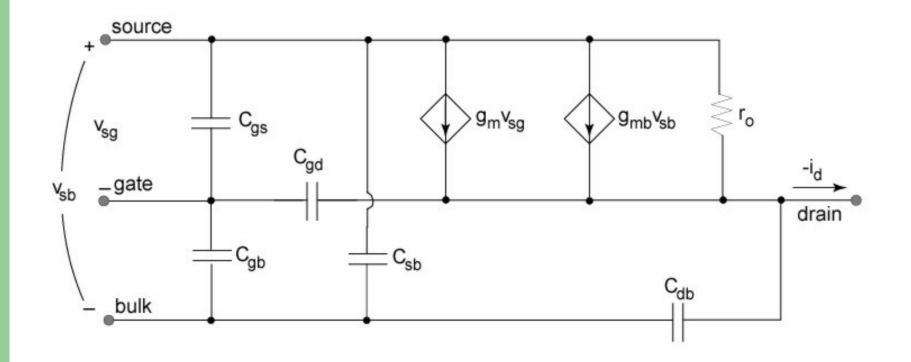
Measurement of $-I_{Dp}$ versus V_{SD} , with V_{SG} as a parameter:



Square-Law PMOS Characteristics



Small-Signal PMOS Model



MOSFET SPICE Model

Many "levels" ... we will use the square-law "Level 1" model See H&S 4.6 + Spice refs. on reserve for details.

.MODEL MODN NMOS LEVEL = 1 VTO = 1 KP = 50U LAMBDA = .033 GAMMA = .6 + PHI = 0.8 TOX = 1.5E-10 CGDO = 5E-10 CGSO = 5E-10 CJ = 1E-4 CJSW = 5E-10 + MJ = 0.5 PB = 0.95

.MODEL MODP PMOS LEVEL = 1 VTO = -1 KP = 25U LAMBDA = .033 GAMMA = .6 + PHI = 0.8 TOX = 1.5E-10 CGDO = 5E-10 CGSO = 5E-10 CJ = 3E-4 CJSW = 3.5E-10 + MJ = 0.5 PB = 0.95